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<div style="display: flex; justify-content: space-between;"> <div style="width: 45%;"> <p>(21) Internationales-Aktenzeichen: PCT/EP00/00815</p> <p>(22) Internationales Anmeldedatum: 2. Februar 2000 (02.02.00)</p> <p>(30) Prioritätsdaten:  199 06 852.6      18. Februar 1999 (18.02.99)      DE  199 26 462.7      10. Juni 1999 (10.06.99)      DE</p> <p>(71) Anmelder (für alle Bestimmungsstaaten ausser US): STEAG MICROTECH GMBH [DE/DE]; Carl-Benz-Strasse 10, D-72124 Pliezhausen (DE).</p> <p>(72) Erfinder; und  (75) Erfinder/Anmelder (nur für US): OSHINOWO, John [DE/DE]; Mörikestrasse 14, D-72667 Schlaitdorf (DE). BIEBL, Ulrich [DE/DE]; Friedhofstrasse 10, D-79297 Winden (DE).</p> <p>(74) Gemeinsamer Vertreter: STEAG MICROTECH GMBH; Steag AG, Zentralbereich Recht und Patente, D-45117 Essen (DE).</p> </div> <div style="width: 50%;"> <p>(81) Bestimmungsstaaten: JP, KR, US, europäisches Patent (AT, BE, CH, CY, DE, DK, ES, FI, FR, GB, GR, IE, IT, LU, MC, NL, PT, SE).</p> <p><b>Veröffentlicht</b> <i>Mit internationalem Recherchenbericht.</i></p> </div> </div>		

(54) Title: METHOD AND DEVICE FOR TREATING SUBSTRATES

(54) Bezeichnung: VORRICHTUNG UND VERFAHREN ZUM BEHANDELN VON SUBSTRATEN

(57) Abstract

The aim of the invention is to increase the throughput capacity of a conventional substrate treatment device by essentially maintaining the floor space required. To this end, a device and a method for treating substrates in at least one of two basins is provided. Said basins can be filled with at least two treatment fluids. The method comprises the following steps: a) processing a first treatment fluid in a processing unit that is shared by the two basins, b) charging the basin with substrates, c) passing at least the second treatment fluid into the basin and e) removing the substrates from the basin, whereby the processing steps in the relevant basins are controlled at staggered intervals in such a way that a time period is provided between the end of step c) in one of the basins and the beginning of step c) in another basin, whereby said time period is sufficiently long for processing the first treatment fluid.

